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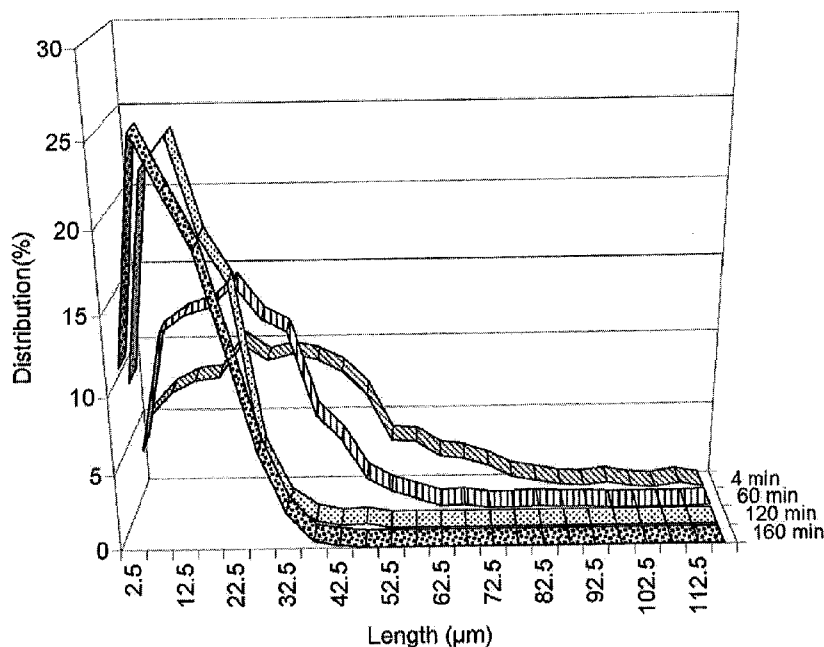
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(54) Title: METHODS FOR CONTROLLING METAL NANOSTRUCTURES MORPHOLOGY

**FIG. 11**

(57) Abstract: Described herein are
 methods of controlling metal
 nanowire morphologies by adjusting
 the reaction conditions of a polyol
 synthesis. In particular, by purging
 the reaction with an inert gas, batch-
 to-batch consistency can be achieved.



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